

THE CLAIMS

WHAT IS CLAIMED IS:

- 1 1. A cleaning or photoresist stripping composition comprising:
2 (a) from about 5% to about 50% by weight of a polar aprotic nitrogen-
3 containing solvent having a dipole moment of more than about 3.5;
4 (b) from about 0.2% to about 20% by weight of a choline derivative
5 selected from the group consisting of a bis-choline salt, a tris-choline salt, and a mixture
6 thereof; and
7 (c) from about 50% to about 94% by weight of a sulfur-containing solvent
8 selected from the group consisting of a sulfoxide, a sulfone, and a mixture thereof.
- 1 2. The composition of claim 1, wherein the polar aprotic nitrogen-containing
2 solvent comprises N-methyl-2-pyrrolidone.
- 1 3. The composition of claim 1, wherein the polar aprotic nitrogen-containing
2 solvent is present in an amount from about 15% to about 35% by weight,
- 1 4. The composition of claim 3, wherein the polar aprotic nitrogen-containing
2 solvent is present in an amount from about 20% to about 30% by weight.
- 1 5. The composition of claim 4, wherein the polar aprotic nitrogen-containing
2 solvent is present in an amount from about 24% to about 26% by weight.
- 1 6. The composition of claim 1, wherein the choline derivative is present in an
2 amount from about 0.5% to about 10% by weight.
- 1 7. The composition of claim 6, wherein the choline derivative is present in an
2 amount from about 1% to about 5% by weight.
- 1 8. The composition of claim 7, wherein the choline derivative is present in an
2 amount from about 1% to about 3% by weight.
- 1 9. The composition of claim 1, wherein the sulfur-containing solvent
2 comprises dimethyl sulfoxide, methyl sulfoxide, or a mixture thereof.

1 10. The composition of claim 9, wherein the sulfur-containing solvent is present
2 in an amount from about 60% to about 84% by weight.

1 11. The composition of claim 10, wherein the sulfur-containing solvent is
2 present in an amount from about 66% to about 76% by weight.

1 12. The composition of claim 11, wherein the sulfur-containing solvent is
2 present in an amount from about 70% to about 72% by weight.

1 13. The composition of claim 1, which is further substantially free of water.

1 14. The composition of claim 1, which is further substantially free of one or
2 more of the following: additional amines, additional corrosion inhibitors, additional
3 chelating agents, additional surfactants, additional organic solvents, additional acids, and
4 additional bases.

1 15. The composition of claim 14, which is further substantially free of all of the
2 following: additional amines, additional corrosion inhibitors, additional chelating agents,
3 additional surfactants, additional organic solvents, additional acids, and additional bases.

1 16. The composition of claim 1, further comprising up to about 10% by weight
2 of water.

1 17. A cleaning or photoresist stripping composition consisting essentially of:
2 (a) from about 5% to about 50% by weight of a polar aprotic nitrogen-
3 containing solvent having a dipole moment of more than about 3.5;
4 (b) from about 0.2% to about 20% by weight of a choline derivative
5 selected from the group consisting of a bis-choline salt, a tris-choline salt, and a mixture
6 thereof; and
7 (c) from about 50% to about 94% by weight of a sulfur-containing solvent
8 selected from the group consisting of a sulfoxide, a sulfone, and a mixture thereof.

1 18. The composition of claim 17, wherein the polar aprotic nitrogen-containing
2 solvent comprises N-methyl-2-pyrrolidone.

1 19. The composition of claim 17, wherein the polar aprotic nitrogen-containing
2 solvent is present in an amount from about 15% to about 35% by weight.

1 20. The composition of claim 19, wherein the polar aprotic nitrogen-containing
2 solvent is present in an amount from about 20% to about 30% by weight.

1 21. The composition of claim 17, wherein the choline derivative is present in an
2 amount from about 0.5% to about 10% by weight.

1 22. The composition of claim 21, wherein the choline derivative is present in an
2 amount from about 1% to about 5% by weight.

1 23. The composition of claim 17, wherein the sulfur-containing solvent
2 comprises dimethyl sulfoxide, methyl sulfoxide, or a mixture thereof.

1 24. The composition of claim 23, wherein the sulfur-containing solvent is
2 present in an amount from about 60% to about 84% by weight.

1 25. The composition of claim 24, wherein the sulfur-containing solvent is
2 present in an amount from about 66% to about 76% by weight.